

Laser-Based Digital Microfabrication

Alberto Piqué, Heungsoo Kim, Ray Auyeung, Jiwen Wang, Andrew Birnbaum and Scott Mathews
Materials Science and Technology Division, Code 6364, Naval Research Laboratory, Washington, DC 20375

Abstract

Non-lithographic digital microfabrication processes are ideally suited for the rapid prototyping of microelectronic devices and other high fidelity micro-components. Laser Direct-Write is an example of digital microfabrication that offers unique advantages and capabilities. A key advantage of laser direct-write techniques is their compatibility with a wide range of materials, surface chemistries and surface morphologies. The Naval Research Laboratory has developed various laser-based forward transfer processes ranging from the non-phase transformative direct printing of complex suspensions or inks to the "lase-and-place" of entire semiconductor devices. These processes have been demonstrated in the fabrication of a wide variety of microelectronic elements such as interconnects, passives, antennas, sensors, power sources and embedded circuits. Recently, laser direct-write of thin film-like structures with excellent lateral resolution and thickness uniformity using metallic nano-inks has also been demonstrated. The high degree of control in size and shape achievable was applied to the digital microfabrication of 3-dimensional stacked assemblies and also MEMS-like structures. Overall, the application of laser-based direct-write techniques is well suited for the development, customization, modification, and repair of microelectronic components and systems. This paper will provide a brief introduction to laser direct-write and describe several examples of the types of structures and devices fabricated at NRL using laser-based digital microfabrication processes.

Introduction

Lithography and etching processes have reigned supreme in the micro and nanofabrication areas since the beginning of the microelectronics industry. There are considerable challenges, however, in adapting lithographic processes to new applications requiring processing on plastic or flexible substrates, production of small batch sizes and customization or prototype redesign. In these cases, the complexity, significant capital investment and high operating costs of the equipment involved, combined with the limited range of materials that can be patterned represent significant shortcomings. Furthermore, the use of lithographic techniques requiring the vacuum deposition of a thin film and its subsequent etching to achieve a desired pattern from a given material is not practical for many applications requiring the modification, and/or repair of existing microelectronic devices or circuits. As a result, there is a pressing need for the development of new microfabrication techniques and approaches that avoid these limitations.

An alternative to lithography is provided by direct-write techniques. Direct-write techniques are digital microfabrication processes that allow the formation of patterns or structures under complete computer control. Examples of direct-write techniques

include inkjet, laser chemical vapor deposition or LCVD and laser direct-write or LDW. In general, these non-lithographic techniques allow the deposition of individual 3-dimensional pixels or "voxels" of virtually any type of material at precisely defined locations to generate a given pattern or shape with little or no material waste. For applications requiring the modification or repair of an existing microelectronic circuit or device, direct-write techniques offer the best chance for success. However, most direct-write techniques are not capable of depositing patterns of electronic materials with placement precision under a micron, with uniform thickness of a few hundred nanometers and with feature morphology and size similar to the surrounding thin film structures already present in the lithographically processed device or circuit. This has limited their use and implementation outside the laboratory.

Laser direct-write is a digital microfabrication process compatible with a wide range of materials and substrates. The Naval Research Laboratory (NRL) has developed various laser direct-write (LDW) techniques with unique capabilities ranging from the non-phase transformative direct printing of complex suspensions or inks [1] to the "lase-and-place" of entire semiconductor devices [2]. More recently, the use of high viscosity metallic nano-inks with LDW has allowed the direct printing of thin film-like structures with excellent lateral resolution and thickness uniformity [3].

Background

Some direct-write processes, like LCVD, can produce thin-film-like patterns, but are limited by their slow deposition rate, narrow choice of materials, and complexity, including the need for operating in vacuum. Other simpler additive direct-write processes like inkjet can operate without the need for a vacuum and at room temperature. However, despite inkjet's inherent simplicity, achieving pattern resolutions under 5 micrometers on different types of substrate surfaces is very challenging with inks containing electronic materials such as metals or ceramics.

LDW is not limited by the constraints encountered in LCVD or inkjet. The term laser direct-write includes various techniques such as laser-based modification, subtraction and addition processes that can create patterns of materials directly on substrates without the need for lithography or masks. In additive mode, laser-forward transfer processes are used for the deposition of voxels, i.e. 3D pixels, of metals, oxides, polymers and composites under ambient conditions onto virtually any type of surface. This laser printing process has been used with great success in the fabrication of sensors, microbatteries, interconnects, antennae and solar cells [4-6]. When combined with other laser forward transfer processes, LDW can be used for fabricating embedded electronic devices and circuits [7]. LDW is also capable of transferring entire devices such as semiconductor IC's inside a pocket or recess in a substrate, similar to pick-and-place machines

used in circuit board assembly [8]. No other direct-write technique offers this broad range of capabilities for the rapid prototyping of electronic circuits on a single platform. A schematic illustrating the basic components of a laser direct-write system is shown in Figure 1.

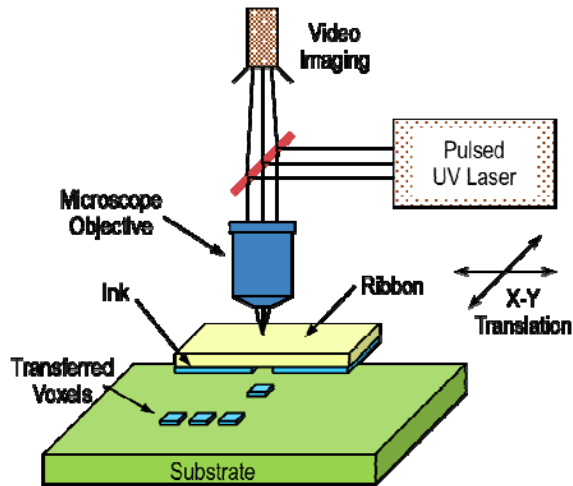


Figure 1. Schematic showing the basic components of a laser direct-write system.

Experimental

The laser used for the transfers performed in this work was a frequency tripled Nd:YVO₄ laser operating at 355 nm with pulse energies of a few hundred μJ at kHz repetition rates. Typical laser energies used for laser transfer were ~ 2 to 10 nJ (30 ns FWHM) resulting in a fluence of 8 to 40 mJ/cm^2 at the ribbon. The substrate was placed on top of a computer-controlled X-Y stage motion control system. The ribbon was made from a 50 mm x 75 mm glass microscope slide to which a suspension of silver nanoparticles (called the ink) was applied using doctor blading and placed with the ink layer side parallel and facing the receiving substrate separated by a 10 to 50 microns adjustable gap. The laser spot was focused onto this ink layer and a series of voxels were laser decal transferred by translating the ribbon to a new area after each laser pulse. Transfers were performed on a variety of surfaces including polyimide, glass and p-type Silicon. The surface of the substrates was not pre-treated by any special techniques other than rinsing with organic solvents (acetone and isopropanol) and dried with nitrogen. After transfer, the samples were placed in a convection oven for 30 min. at 200 °C for thermal curing.

Optical microscopy was used to characterize the transfers before and after curing and also to characterize the ribbon before and after the transfers. Once cured, the thickness, width and surface morphology of the transfers were determined using contact profilometry (KLA Tencor P-10), atomic force microscopy or AFM (Digital Instruments Dimension 3100), and scanning electron microscopy or SEM (LEO 1550). The adhesion and chemical resistance were evaluated by subjecting the transfers to tape peel tests and immersion in solvents (water and isopropanol) respectively, and afterwards measuring any changes in morphology or electrical properties of the transferred patterns. Characterization of the electrical properties of sample lines

transferred between Au-pads on glass substrates was performed using standard 4-probe measurement techniques using a Keithley 2400 sourcemeter with 200 μA input current.

Results and Discussion

Comparison of the size of the removed material on the ribbon with the resulting transfer demonstrated that the laser transfer resulted in virtually a 1-to-1 correspondence in size and shape between the laser spots illuminating the ribbon and the transferred voxels. This is very important for repair applications, since specific voxel lengths and forms can be generated with a variable shape aperture, allowing the transfer of a complete repair pattern with one single laser pulse. In general, the thickness of the transfers depended on the thickness of the ink layer on the ribbon and ranged between 100 nm and 1 μm . For any given thickness, however, AFM analysis of the transfers demonstrated the excellent edge definition and thickness uniformity of the laser transfers. Such features are similar to those obtained by lithographically patterning and then etching a vacuum deposited thin film layer of similar thickness. To our knowledge, no other laser forward transfer technique can generate the kind of thin film-like patterns that can be achieved using our approach, which we have named laser decal transfer.

The use of high viscosity nanoparticle suspensions (1,000 to 100,000 cP) as inks for the ribbon plays an important role in the ability to perform the decal transfers. To date, most of the nano-inks used in laser transfers by other groups have been of relatively low viscosities (< 100 cP) and the resulting transfers form droplets when released from the ribbon. As the droplets reach the substrate surface, patterns of varying shape and thicknesses tend to be generated analogous to those formed by inkjet, but with surrounding debris. By using nanoparticle suspensions of much higher viscosities, it is possible to take advantage of shear thickening effects that prevent the breakup of the transfer into a discontinuous ensemble. This is the basis of the process called laser decal transfer developed at NRL for the laser printing of complex suspensions using thin layers of higher viscosity pastes applied to the ribbons [3].

In order to characterize the electrical properties of the laser decal transfers, multiple sets of continuous lines across gold pads on glass substrates were printed and then oven cured. As shown in Figure 2(a), each line was made by laser decal transfer of individual 15 μm x 5 μm voxels printed next to each other. Electrical characterization using 4-probe measurements revealed resistivities for some of these lines to be as low as 3.4 $\mu\Omega$ cm, which corresponds to about 2.1 times the resistivity of bulk silver metal (1.6 $\mu\Omega$ cm at room temperature). Figure 2(b) shows a more complex line pattern made from the combination of two different shaped voxels (rectangle and rounded corner) rotated as necessary to form the “s” shaped line. The SEM image on Figure 2(c) shows how the adjacent voxels coalesce once transferred forming uniform and continuous lines on the substrate surface. This merging of individual voxels into one continuous pattern is unique to the non-phase transforming laser transfer of rheological fluids and impossible to achieve with traditional laser induced forward transfer (known in the literature by the acronym LIFT), which relies on the vaporization or melting of the transferred material [1]. The ability to laser decal transfer complex fluids and suspensions without degrading their properties while maintaining their shape

and thickness once released from the ribbon is crucial for printing highly conductive thin-film-like patterns devoid of discontinuities, interfaces or steps.

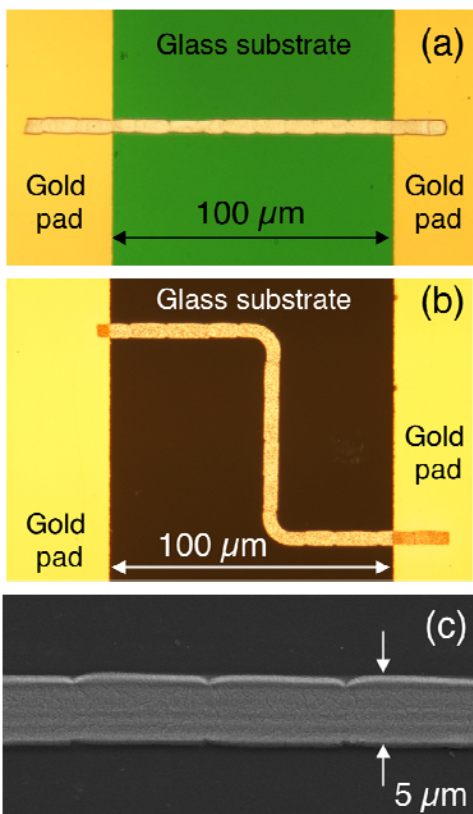


Figure 2. Optical and SEM micrographs showing conductive silver lines made by laser decal transfer of individual silver nano-ink voxels across gold pads on glass substrates. (a) Line made from 15 μm long x 5 μm wide adjacent voxels; (b) line made by combining the rectangular voxels from (a) with corner shaped ones; (c) SEM image showing a section from the line in (a). Note the continuous pattern across adjacent voxels.

Since laser decal transfer is able to generate patterns with high edge definition and low debris outside the transferred region, it is also well suited for the deposition of patterns or lines in close proximity or with small gaps. This is very important for fabricating high density interconnects and electrodes for organic thin film transistors. Figure 3 shows an example of source and drain inter-digitated electrodes laser printed onto a pentacene layer for a working organic thin film transistor device. The properties of these organic thin film transistors with laser printed electrode have been shown to be of very high quality [9].

The high degree of control in size and shape of the transferred voxels achievable with laser decal transfer can in principle also be used to build 3-dimensional stacked structures. Such capability represents a true digital microfabrication process by which complex geometries can be generated voxel by voxel. This capability is unique and opens the possibility for the digital microfabrication of other types of structures such as MEMS on low temperature substrates, which are impossible to generate by lithographic techniques. Examples of various structures made by

LDW of high viscosity inks using the laser decal transfer technique are shown in Figure 4.

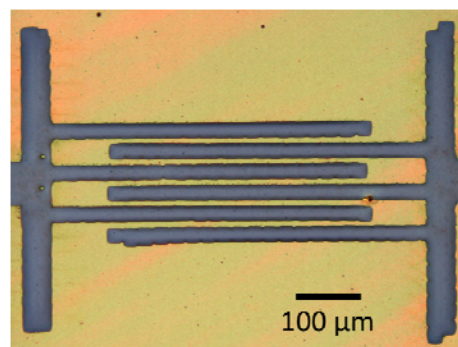


Figure 3. Optical micrograph showing the top source and drain electrodes laser printed over the pentacene layer of an organic thin film transistor.

Summary

Laser printing or LDW of high viscosity inks results in digitally microfabricated patterns that exhibit extremely uniform thickness, show precise edge definition and are free of debris. Given that laser decal transfer allows the printing of different shapes and sizes, any given pattern can be deposited in just a few steps, thus allowing further optimization of the writing time. In fact, LDW using laser decal transfers correspond to a form of digital microfabrication processes where the shape and size of each “bit” can be changed at will. The resulting decal transfers are well suited for the repair, modification and customization of microelectronic circuits, such as TFT-FPD’s, photovoltaics, integrated circuits and other semiconductor devices, as well as the direct-write of MEMS-like three-dimensional structures.

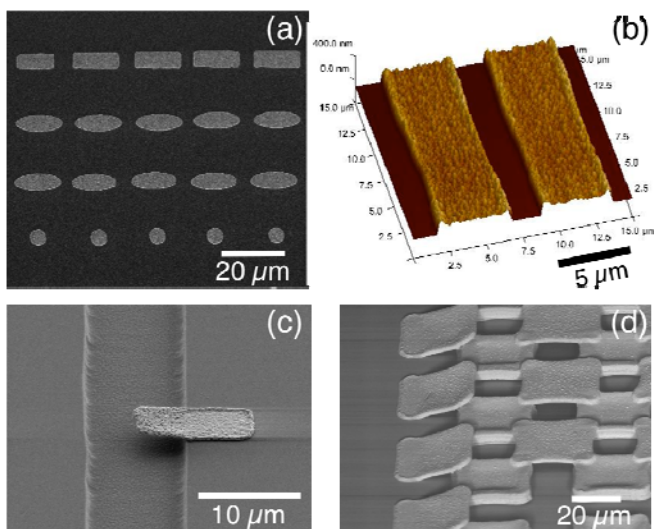


Figure 4. Sample structures made by laser decal transfer: (a) SEM of individual voxels as a function of aperture shape; (b) AFM of 5 μm wide Ag lines with 2 μm gap; (c) SEM of a free standing Ag cantilever; and (d) SEM of stacked 30 μm Ag square pads forming pillars and free standing structures. No sacrificial layers were used to produce the freestanding structures shown in (c) & (d).

Acknowledgements

This work was sponsored by the U.S. Office of Naval Research

References

- [1] C.B. Arnold, P. Serra and A. Piqué, MRS Bulletin, **32**, 23 (2007).
- [2] S.A. Mathews, N.A. Charipar, K. Metkus and A. Piqué, Photonics Spectra, **41** No. 10, pg. 70 (2007).
- [3] A. Piqué, R.C.Y. Auyeung, H. Kim, K.M. Metkus and S.A. Mathews, J. Laser Micro/Nanoeng., **3**, 163 (2008).
- [4] H. Kim, R.C.Y. Auyeung and A. Piqué, J. Power Sources, **165**, 413 (2007).
- [5] H. Kim, G.P. Kushto, C.B. Arnold, Z.H. Kafafi and A. Piqué, Appl. Phys. Lett., **85**, 464 (2004).
- [6] R.C.Y. Auyeung, M.W. Nurnberger, D.J. Wendland, A. Piqué, C.B. Arnold, A.R. Abbott and L.C. Schuette, SPIE Proc., **5339**, 292 (2004).
- [7] A. Piqué, S.A. Mathews, B. Pratap, R.C. Auyeung, B.J. Karns and S. Lakeou, J. Microelectron. Eng., **83**, 2527 (2006).
- [8] S.A. Mathews, R.C.Y. Auyeung and A. Piqué, J. Laser Micro/Nanoeng., **2**, 103 (2007).
- [9] H. Kim, R.C.Y. Auyeung, S.H. Lee, B. Huston and A. Piqué, Appl. Phys. A, **96**, 441 (2009).

Author Biography

Dr. Alberto Piqué is Head of the Electronics and Optical Materials & Devices Section at the U.S. Naval Research Laboratory. He is a recognized expert in the field of direct-write and laser forward transfer and the use of these techniques for the fabrication of microelectronics, micropower sources and sensors